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Patent  
Attorney's Docket No. 015290-506

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Patent Application of	)	
	)	
Ting CHIEN et al.	)	Group Art Unit: 1765
	)	
Application No.: 09/820,692	)	Examiner: K.C. Chen
	)	
Filed: March 30, 2001	)	Confirmation No. 5245
	)	
For: PLASMA ETCHING OF DIELECTRIC LAYER	)	
WITH SELECTIVITY TO STOP LAYER	)	
	)	

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JUL 25 2003  
GROUP 1700

REQUEST FOR RECONSIDERATION

Assistant Commissioner for Patents  
Washington, D.C. 20231

Sir:

Reconsideration of the Official Action dated May 28, 2003 is respectfully requested.

REMARKS

Claims 1-25 are pending in the application for the Examiner's review and consideration.

First Rejection

Claims 23-25 were rejected under 35 U.S.C. § 112, first paragraph, for allegedly containing subject matter not described in the specification. This rejection is respectfully traversed for the following reasons. Claim 23 is directed to an etchant gas that is *hydrogen-free*. In the Advisory Action dated September 22, 2002, the rejection of Claim 23 (which is directed to a "hydrogen-free" etchant gas) was withdrawn. Accordingly, the Examiner